# EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|---|---|---|---|---|---|---|
| L1 | 13483 | 134/1,2,26,29,902.ccls. 355/53.ccls. | US-PGPUB; USPAT | OR | ON | 2009/02/11 12:28 |
| L2 | 267 | 1 and ((immersion near3 lithography)) and ((clean$3 or wash$3 or remov$3 or treat$5) same (len or optical or optic)) | US-PGPUB; USPAT | OR | ON | 2009/02/11 12:28 |
| L3 | 17 | 2 and ("h.sub.2o.sub.2" or "hydrogen peroxide" or ozone or "o.sub.3") | US-PGPUB; USPAT | OR | ON | 2009/02/11 12:29 |
| S2 | 2 | "20050205108".pn. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/09 14:58 |
| S3 | 1 | "7420188".pn. | US-PGPUB; USPAT | OR | ON | 2009/02/09 15:03 |
| S4 | 1 | "7056646".pn. | US-PGPUB; USPAT | OR | ON | 2009/02/09 15:05 |
| S6 | 2 | "20060023185".pn. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/09 15:24 |
| S7 | 1 | "6788477".pn. | US-PGPUB; USPAT | OR | ON | 2009/02/09 15:26 |
| S8 | 1 | "5368649".pn. | US-PGPUB; USPAT | OR | ON | 2009/02/09 15:31 |
| S9 | 2 | "6496257".pn. "5368649". pn. | US-PGPUB; USPAT | OR | ON | 2009/02/09 15:41 |
| S11 | 4 | "874283".pn. | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/09 15:41 |
| S15 | 840 | ((immersion near3 lithography)) and ((clean$3 or wash$3 or remov$3 or treat$5) same (len or optical or optic)) | US-PGPUB; USPAT | OR | ON | 2009/02/09 16:02 |
| S16 | 18 | S15 and "134".clas. | US-PGPUB; USPAT | OR | ON | 2009/02/09 16:02 |

| S17 | 70 | ((immersion near3 lithography)) and ((clean$3 or wash$3 or remov$3 or treat$5) same (len or optical or optic)) | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/09 16:21 |
|---|---|---|---|---|---|---|
| S18 | 0 | S17 and b08b$/$.ipc. | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/09 16:21 |
| S19 | 11 | S17 and h01l$/$.ipc. | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/09 16:21 |
| S20 | 32 | ((immersion near3 lithography) same (clean$3 or wash$3 or remov$3 or treat$5) same (len or optical or optic)) | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/09 16:21 |
| S21 | 59 | S17 not S19 | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/09 16:39 |
| S22 | 30 | S21 not S20 | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/09 16:39 |
| S23 | 1 | "4046706".pn. | US-PGPUB; USPAT | OR | ON | 2009/02/09 16:53 |
| S24 | 46 | ("20010002315" \| "3648587" \| "4057347" \| "4480910" \| "5121256" \| "5139661").PN. OR ("6788477").URPN. | US-PGPUB; USPAT; USOCR | OR | ON | 2009/02/09 17:05 |
| S25 | 1 | "7056646".pn. | US-PGPUB; USPAT | OR | ON | 2009/02/09 18:15 |
| S26 | 5 | "2004093130".pn. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/09 18:19 |
| S27 | 1 | "7070915".pn. | US-PGPUB; USPAT | OR | ON | 2009/02/09 18:37 |
| S28 | 11 | ((immersion near3 lithography)) same expos$3 same surfactant same (liquid or fluid) | US-PGPUB; USPAT | OR | ON | 2009/02/09 19:14 |
| S29 | 2 | "20050164502".pn. "20050161644".pn. | US-PGPUB; USPAT | OR | ON | 2009/02/10 09:55 |

| S30 | 51 | (immersion near3 lithography) and (immersion same (fluid or liquid) same surfactant) | US-PGPUB; USPAT | OR | ON | 2009/02/10 09:57 |
| S31 | 111 | ((immersion near3 lithography) same (clean$3 or wash$3 or remov$3)) and (surfactant) | US-PGPUB; USPAT | OR | ON | 2009/02/10 11:13 |
| S32 | 8 | S31 and "134".clas. | US-PGPUB; USPAT | OR | ON | 2009/02/10 11:14 |
| S33 | 8 | ((immersion near3 lithography) same (clean$3 or wash$3 or remov$3)) and (surfactant) | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 11:14 |
| S34 | 14 | S31 and @ad<"20040316" | US-PGPUB; USPAT | OR | ON | 2009/02/10 11:15 |
| S35 | 5 | (lithography same (clean$3 or wash$3 or remov$3) same (len or optical)) and (surfactant) | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 11:19 |
| S36 | 213 | (lithography same (clean$3 or wash$3 or remov$3) same (len or optical)) and (surfactant) | US-PGPUB; USPAT | OR | ON | 2009/02/10 11:20 |
| S37 | 8 | S36 and "134".clas. | US-PGPUB; USPAT | OR | ON | 2009/02/10 11:20 |
| S38 | 493 | (lithography same (clean$3 or wash$3 or remov$3) same (len or optical)) and ("nh.sub.4oh" or "ammonium hydroxide" or ozone or "o.sub.3" or "hydrogen peroxide" or "h.sub.2o.sub.2") | US-PGPUB; USPAT | OR | ON | 2009/02/10 11:55 |
| S39 | 19 | S38 and "134".clas. | US-PGPUB; USPAT | OR | ON | 2009/02/10 11:55 |
| S40 | 13 | (lithography same (clean$3 or wash$3 or remov$3) same (len or optical)) and ("nh.sub.4oh" or "ammonium hydroxide" or ozone or "o.sub.3" or "hydrogen peroxide" or "h.sub.2o.sub.2") | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 11:57 |
| S41 | 10 | (lithography same (clean$3 or wash$3 or remov$3) same (len or optical)) and (ozone or "o.sub.3" or "hydrogen peroxide" or "h.sub.2o.sub.2") | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 12:20 |

| S42 | 393 | (lithography same (clean$3 or wash$3 or remov$3) same (len or optical)) and (ozone or "o.sub.3" or "hydrogen peroxide" or "h.sub.2o.sub.2") | US-PGPUB; USPAT | OR | ON | 2009/02/10 12:20 |
|-----|-----|-----|-----|-----|-----|-----|
| S43 | 19 | S42 and "134".clas. | US-PGPUB; USPAT | OR | ON | 2009/02/10 12:20 |
| S44 | 165 | surfactant same hydrophilic same wafer | US-PGPUB; USPAT | OR | ON | 2009/02/10 13:03 |
| S45 | 4 | S44 and (immersion near3 lithography) | US-PGPUB; USPAT | OR | ON | 2009/02/10 13:04 |
| S46 | 65 | surfactant with hydrophilic with wafer | US-PGPUB; USPAT | OR | ON | 2009/02/10 13:09 |
| S47 | 2 | "9949504".pn. | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 14:18 |
| S48 | 10 | ((immersion near3 lithography) same ((deionized or "de-ionized") near2 water)) | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 14:20 |
| S49 | 157 | ((immersion near3 lithography) same ((deionized or "de-ionized") near2 water)) | US-PGPUB; USPAT | OR | ON | 2009/02/10 14:22 |
| S51 | 1 | "7315033".pn. | US-PGPUB; USPAT | OR | ON | 2009/02/10 16:06 |
| S52 | 11 | ("20040125351" \| "20040207824" \| "20040257544" \| "20050007570" \| "20050018155" \| "20050024609" \| "20050078286" \| "20060132731" \| "6466365" \| "6496257" \| "7145641").PN. OR ("7315033").URPN. | US-PGPUB; USPAT; USOCR | OR | ON | 2009/02/10 16:06 |
| S54 | 4 | S52 and (ozone or "o.sub.3" or "hydrogen peroxide" or "h.sub.2o.sub.2") | US-PGPUB; USPAT | OR | ON | 2009/02/10 16:07 |
| S56 | 2 | "7315033".pn. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 16:12 |

| S58 | 747 | ((clean$3 or remov$3 or wash$3) same (len or optical)) and (ozone or "o.sub.3" or "hydrogen peroxide" or "h.sub.2o.sub.2") | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 16:20 |
|---|---|---|---|---|---|---|
| S61 | 25 | S58 and b08b$/$.ipc. | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 16:23 |
| S73 | 25 | ("4021120" \| "4074217" \| "4365877" \| "4365896" \| "4896047" \| "5088083" \| "5229602" \| "5812270" \| "5929981" \| "6268904").PN. OR ("6496257").URPN. | US-PGPUB; USPAT; USOCR | OR | ON | 2009/02/10 16:34 |
| S77 | 21 | ((clean$3 or remov$3 or wash$3) same (len or optical)) and ((ozone or "o.sub.3") same ("hydrogen peroxide" or "h.sub.2o.sub.2")) | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 16:56 |
| S78 | 3 | "7119878".pn. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 17:00 |
| S79 | 633 | ((clean$3 or remov$3 or wash$3) same (len or optical)) and ((ozone or "o.sub.3") same ("hydrogen peroxide" or "h.sub.2o.sub.2")) | US-PGPUB; USPAT | OR | ON | 2009/02/10 17:02 |
| S80 | 87 | S79 and "134".clas. | US-PGPUB; USPAT | OR | ON | 2009/02/10 17:02 |
| S81 | 50 | S80 and @ad<"20040316" | US-PGPUB; USPAT | OR | ON | 2009/02/10 17:02 |
| S82 | 1279 | ((clean$3 or remov$3 or wash$3) same (ozone or "o.sub.3") same ("hydrogen peroxide" or "h.sub.2o.sub.2")) and (lithography or exposure) | US-PGPUB; USPAT | OR | ON | 2009/02/10 17:04 |
| S83 | 149 | S82 and "134".clas. | US-PGPUB; USPAT | OR | ON | 2009/02/10 17:05 |
| S84 | 102 | S83 and @ad<"20040316" | US-PGPUB; USPAT | OR | ON | 2009/02/10 17:05 |
| S85 | 78 | S84 not S81 | US-PGPUB; USPAT | OR | ON | 2009/02/10 17:05 |

| S87 | 2 | "10289853".pn. | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 17:27 |
|---|---|---|---|---|---|---|
| S92 | 1 | "20060005857".pn. | US-PGPUB; USPAT | OR | ON | 2009/02/10 17:36 |
| S93 | 25 | ("4021120" \| "4074217" \| "4365877" \| "4365896" \| "4896047" \| "5088083" \| "5229602" \| "5812270" \| "5929981" \| "6268904"). PN. OR ("6496257").URPN. | US-PGPUB; USPAT; USOCR | OR | ON | 2009/02/10 17:40 |
| S94 | 1 | "6568995".pn. | US-PGPUB; USPAT; USOCR | OR | ON | 2009/02/10 17:46 |
| S95 | 663 | ((clean$3 or remov$3 or wash$3) same (len or optical or lenses)) and ((ozone or "o.sub.3") same ("hydrogen peroxide" or "h.sub.2o.sub.2")) | US-PGPUB; USPAT | OR | ON | 2009/02/10 17:48 |
| S96 | 99 | S95 and "134".clas. | US-PGPUB; USPAT | OR | ON | 2009/02/10 17:48 |
| S97 | 12 | S96 not S80 | US-PGPUB; USPAT | OR | ON | 2009/02/10 17:49 |
| S98 | 1 | "7119878".pn. | US-PGPUB; USPAT | OR | ON | 2009/02/10 17:51 |
| S99 | 6 | US-20040125351-$.DID. OR US-20040207824-$. DID. OR US-20040257544-$.DID. OR US-20050007570-$.DID. OR US-20050018155-$.DID. OR US-20050024609-$. DID. | US-PGPUB; USPAT | OR | ON | 2009/02/10 17:54 |
| S100 | 324 | chang-ching-yu.in. lin-chin-hsiang.in. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 18:16 |
| S101 | 6 | S100 and ((clean$3 or remov$3 or wash$3) same (len or optical or lenses)) and ((ozone or "o.sub.3") same ("hydrogen peroxide" or "h.sub.2o.sub.2")) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 18:16 |
| S103 | 17091 | "taiwan semiconductor manufacturing".as. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 18:19 |

| S104 | 9 | S103 and ((clean$3 or remov$3 or wash$3) same (len or optical or lenses)) and ((ozone or "o.sub.3") same ("hydrogen peroxide" or "h.sub.2o.sub.2")) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/02/10 18:19 |

2/11/2009 12:32:25 PM
C:\Documents and Settings\Sko\My Documents\EAST\Workspaces\Temp Search\10 802 087 (cleaning Immersion lithography).wsp